

# Notice of References Cited

Application No.

08-846671

Applicant(s)

Ko

Examiner

George Goudreau

Group Art Unit

1763

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## U.S. PATENT DOCUMENTS

*	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS
A					
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C					
D					
E					
F					
G					
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## FOREIGN PATENT DOCUMENTS

*	DOCUMENT NO.	DATE	COUNTRY	NAME	CLASS	SUBCLASS
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*	DOCUMENT (including Author, Title, Source, and Pertinent Pages)	DATE
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X		

\* A copy of this reference is not being furnished with this Office action.  
(See Manual of Patent Examining Procedure, Section 707.05(a).)